

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Richard William CHARM et al.

Confirmation No: 6496

Serial No.:

10/689,657

Art Unit:

To be Assigned

Filed:

October 22, 2003

Examiner:

To be Assigned

For:

PROCESS FOR THE USE OF BIS-

Atty Docket No: 060937-0139-US

CHOLINE AND TRIS-CHOLINE IN THE

CLEANING OF QUARTZ-COATED

POLYSILICON AND OTHER MATERIALS

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to applicants' duty of disclosure under 37C.F.R. 1.56, attached is a PTO-1449 citing the thirty-nine (39) references noted in the application for the Examiner's consideration. Copies of the foreign references are enclosed for the Office's convenience (U.S. references are not submitted herewith as this application was filed after June 1, 2003).

No additional fees are believed due, however, should it be deemed fees or credits are due in this matter, the Examiner is authorized to charge/credit Morgan, Lewis & Bockius LLP Deposit Account No. 50-0310.

Respectfully submitted,

Date:

March 2, 2004

Christopher 6. Hayden

Reg., No. 44,750

Morgan, Lewis & Bockius LLP 1111 Pennsylvania Avenue, N.W.

Washington, D.C. 20004

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LIST OF REFERENCES CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Richard William CHARM et al.			
MAR 0 2 2004				FILING DATE October 22, 2003 GROUP To be Assig		signed		
FIFT & TRADE	U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	N.	АМЕ	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	A01							
	A02				-			

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSL	ATION
							YES	NO
	B01	64-42653	01/1989	Japan				
	B02	64-81949	03/1989	Japan				
	B03	62-2813232	12/1987	Japan				
	B04	63-208043	08/1988	Japan				
	B05	11-197523	07/1999	Japan				
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	B07	6-163495	06/1994	Japan				
	B08	6-41773	02/1994	Japan				
	B09	5-181753	07/1993	Japan				
	B10	4-124668	04/1992	Japan				
	B11	4-350660	12/1992	Japan				
	B12	3-227009	10/1991	Japan				
	B13	2-275631	11/1990	Japan				
	B14	1-191450	08/1989	Japan				
	B15						_	
	B16					*	-	
	B17		<u> </u>					-

	OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)
C01	

EXAMINER	DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

ATTY DOCKET NO. APPLICATION NO 060937-0139 10/689,657 REFERENCES CITED BY APPLICANT APPLICANT (Use several sheets if necessary) Richard William CHARM et al. FILING DATE GROUP MAR 0 2 2004 To be Assigned October 22, 2003 TRADEMA

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	A01	4,403,028	09/1983	Ward, Jr. et al.			
	A02	4,172,005	10/1979	Muraoka et al.			
	A03	4,239,661	12/1980	Muraoka et al.			•
	A04	4,294,911	10/1981	Guild		-	
	A05	4,339,340	07/1982	Muroaka et al.			
	A06	4,395,479	07/1983	Ward et al.			
	A07	4,401,747	08/1983	Ward, Jr. et al.			
	A08	4,428,871	01/1984	Ward et al.			
	A09	4,464,461	08/1984	Guild			
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	A11	4,744,834	05/1988	Haq			
	A12	4,770,713	09/1988	Ward			
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	A14	4,904,571	02/1990	Miyashita et al.		٠.	
	A15	5,102,777	04/1992	Lin et al.			
	A16	5,779,791	01/1994	Aldrich et al.			
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	A18	5,334,332	08/1994	Lee			
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	A20	5,417,802	05/1995	Obeng			
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	A22	5,635,423	06/1997	Huang et al.			
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	A26						
	A27						

EXAMINER DATE CONSIDERED	EXAMINER	DATE CONSIDERED
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